

## Measurement of thick films in the thickness range from 1 to 24 $\mu\text{m}$

The accessible film thickness range in spectroscopic ellipsometry using SENTECH **SENresearch 4.0** ellipsometer family is extremely wide. The ellipsometers can measure thicknesses from thin films in the Angstrom range to extremely thick films of about 200  $\mu\text{m}$ . The high spectral resolution of the **SENresearch 4.0** ellipsometer is key for the measurement of extremely thick films.

This application note will discuss the film thickness range from 1.0  $\mu\text{m}$  to 14  $\mu\text{m}$  of a photoresist film and a  $\text{SiO}_2$  film of 25  $\mu\text{m}$  thickness.

This particular film thickness range is accessible using the **SENresearch 4.0** ellipsometer using the basic DUV-VIS spectral range from 240 to 1000 nm. This spectral range is part in all ellipsometers of the **SENresearch 4.0** family.

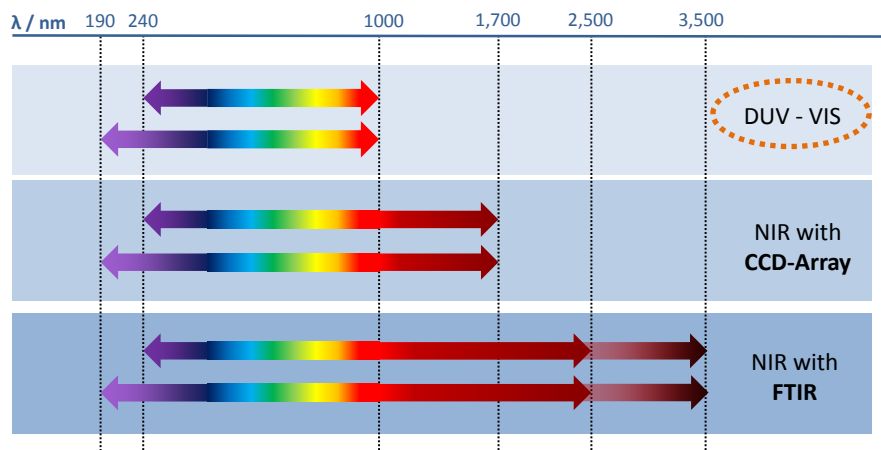


Image 1: **SENresearch 4.0** spectral ranges

Already the basic spectral range of the **SENresearch 4.0** ellipsometers of 240 to 1000 nm will give access to high film thickness of at least up to 25  $\mu\text{m}$ .

## Measurement tool

The **SENresearch 4.0** spectroscopic ellipsometer is used for these measurements. The system is equipped with the basic DUV-VIS spectral range 240 to 1000 nm.

**SpectraRay 4** is the SENTECH comprehensive measurement and analysis software. It is used to perform measurement, modeling, and fitting.



Image 2: **SENresearch 4.0** spectroscopic ellipsometer

## Thick films and technical requirements

Photoresist films are deposited in a wide film thickness range from 1 to 14  $\mu\text{m}$ . They are transparent in the VIS spectral range allowing the accurate measurement of film thickness and the dispersion of optical constants  $n$ ,  $k$ .

Additionally a single  $\text{SiO}_2$  film of 24  $\mu\text{m}$  is prepared and measured.

The high film thickness causes sharp interference fringes which must be resolved accurately by the spectroscopic ellipsometer. The DUV-VIS spectrometer of the **SENresearch 4.0** family features a high spectral resolution allowing access to thick films of at least up to 25  $\mu\text{m}$ .

### Photoresist with film thickness from 1 $\mu\text{m}$ to 14 $\mu\text{m}$

#### Example: Photoresist / Si

Different film thickness of about 1  $\mu\text{m}$ , 3  $\mu\text{m}$ , 6  $\mu\text{m}$ , and 14  $\mu\text{m}$  of photoresist (PR) are prepared.

The optical constants of the photoresist are shown in the following graph.

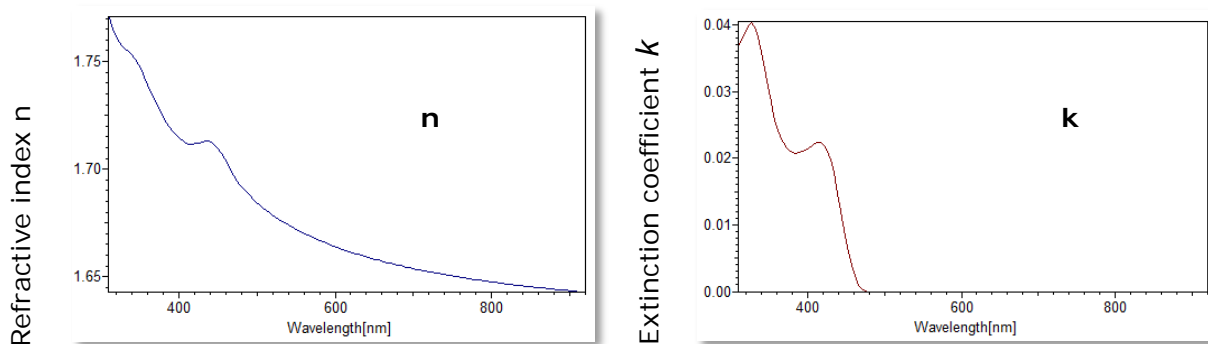


Figure 1: Dispersion of  $n$ ,  $k$  of photoresist

It is transparent in the spectral range from 480 to 920 nm. Below 480 nm a weak extinction can be observed.

## Photoresist film thickness 0.913 $\mu\text{m}$

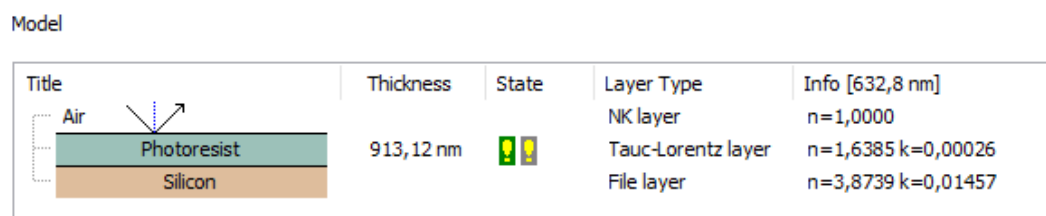


Figure 2: Optical model

The following graph shows the measured ellipsometric  $\Psi$ ,  $\Delta$  spectra of the photoresist / Si sample. On top of the measured spectra the fitted curves are shown in red. The fit quality is excellent; the modeled spectra perfectly fit the measured spectra.

The whole spectral range shows interference fringes originating from the transparent PR film. The number of fringes increases with film thickness.

Below 480 nm a distinct damping of the interference fringes especially visible in the  $\Psi$  spectrum is observed. This is due to the weak extinction of the PR film.

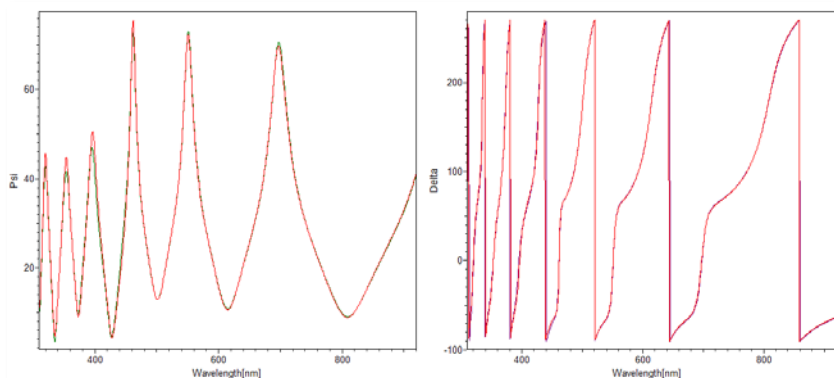


Figure 3: Ellipsometric spectra of 0.913  $\mu\text{m}$  thick photoresist  
The fitted spectral range is 310 to 920 nm

## Photoresist film thickness 3.096 $\mu\text{m}$

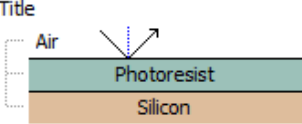

Model				
Title	Thickness	State	Layer Type	Info [632,8 nm]
	3095,94 nm		NK layer	n=1,0000
			Tauc-Lorentz layer	n=1,6594
			File layer	n=3,8739 k=0,01457

Figure 4: Optical model

The PR film is now about three times thicker resulting in three times more and also sharper interference fringes. The spectral resolution of the **SENresearch 4.0** is capable to fully resolve these fringes. The fit quality is excellent.

The damping of the fringes below 480 nm becomes more distinct due to the higher film thickness.

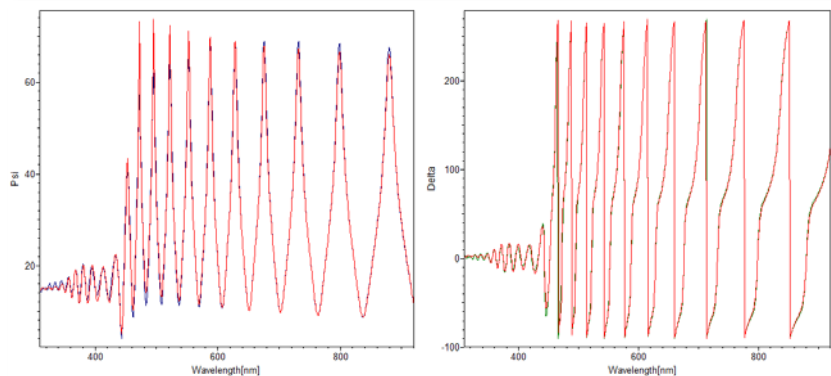


Figure 5: Ellipsometric spectra of 3.096  $\mu\text{m}$  thick photoresist  
The fitted spectral range is 310 to 920 nm

## Photoresist film thickness 5.175 $\mu\text{m}$

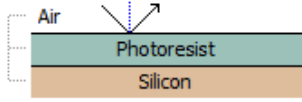
Model				
Title	Thickness	State	Layer Type	Info [632,8 nm]
	5174,82 nm		NK layer	n=1,0000
			Tauc-Lorentz layer	n=1,6405 k=0,00055
			File layer	n=3,8739 k=0,01457

Figure 6: Optical model

The PR film is now more than 5  $\mu\text{m}$  in film thickness. The fringes are still perfectly resolved. The film thickness and optical constants can still be determined accurately.

The damping of the fringes below 480 nm becomes more prominent due to the higher film thickness.

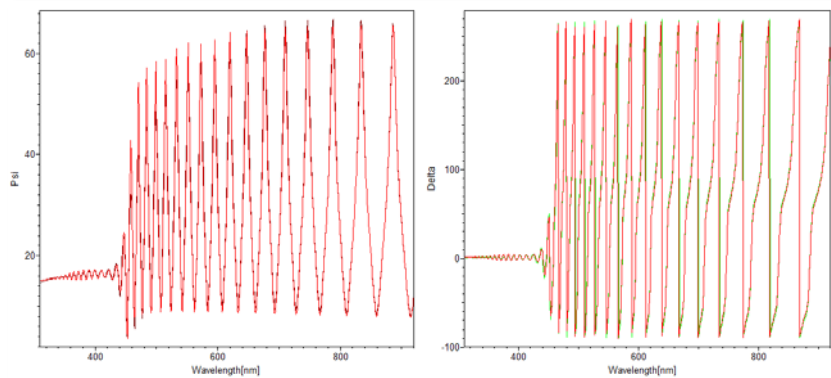


Figure 7: Ellipsometric spectra of 5.175  $\mu\text{m}$  thick photoresist  
The fitted spectral range is 310 to 920 nm

## Photoresist film thickness 13.600 $\mu\text{m}$

Model

Title	Thickness	State	Layer Type	Info [632,8 nm]
Air			NK layer	n=1,0000
Photoresist - TL	13600,00 nm		Tauc-Lorentz layer	n=1,6447
Si DUV-NIR			File layer	n=3,8739 k=0,01457

Figure 8: Optical model

The PR film is distinctly thicker than 10  $\mu\text{m}$ . The number of fringes is increased drastically and a damping of the fringes can be observed due to the spectral resolution of the spectrometer which is 2.1 nm. This spectral resolution is now taken into account into the modelling and fitting procedure.

Limited wavelength resolution

☒ Use limited wavelength resolution

☐ Wavelength resolution:  Calculation steps:

Figure 9: Setting of spectral resolution for the optical modeling

Therefore the fitted curve (red) still perfectly describes the measured spectrum and film thickness and optical constants can be determined accurately.

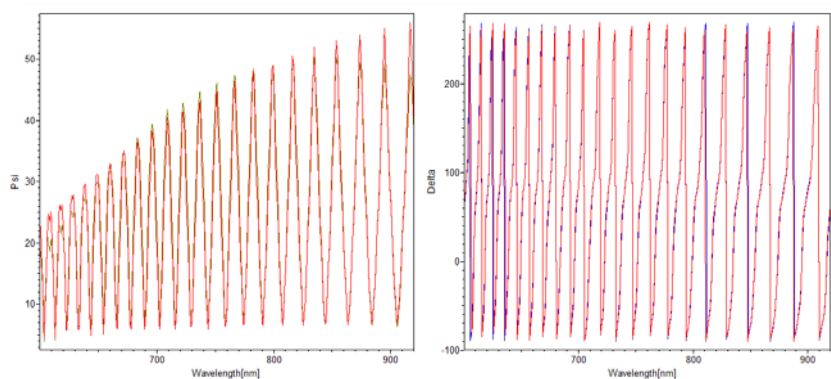


Figure 10: Ellipsometric spectra of 13.600  $\mu\text{m}$  thick photoresist.  
The fitted spectral range is 600 to 920 nm

## SiO<sub>2</sub> film thickness 23.990 μm

Model				
Title	Thickness	State	Layer Type	Info [632,8 nm]
Air			NK layer	n=1,0000
SiO <sub>2</sub>	23990,09 nm	🟢💡	Cauchy layer	n=1,4628
Silicon VIS+NIR			File layer	n=3,8717 k=0,01576

Figure 11: Optical model

The SiO<sub>2</sub> film is 23.990 μm in film thickness and is again distinctly thicker than the PR film. The fringes get sharper and effects of the spectral resolution (damping of the fringes) become more prominent.

The limited spectral resolution is again taken into account for the optical modeling. Therefore the measurement can still be modeled perfectly ensuring accurate results for film thickness and optical constants of the SiO<sub>2</sub> film.

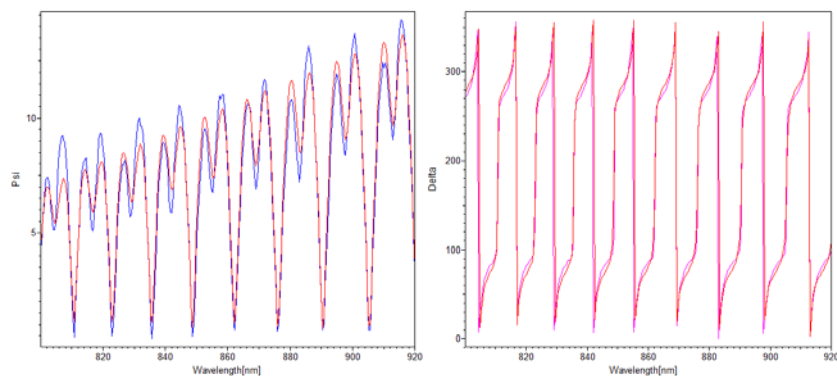


Figure 12: Ellipsometric spectra of 23.990 μm thick SiO<sub>2</sub>.  
The fitted spectral range is 800 to 920 nm